

0/687,689, 7/27/05, Formula 2-1

=> d his All hits for silver halide chem. w/NO E.U. Monomers

(FILE 'HOME' ENTERED AT 14:14:07 ON 27 JUL 2005)

FILE 'REGISTRY' ENTERED AT 14:14:12 ON 27 JUL 2005

L1	STRUCTURE UPLOADED
L2	STRUCTURE UPLOADED
L3	STRUCTURE UPLOADED
L4	5 S L1
L5	98 S L1 FULL
L6	98 S L2 FULL
L7	3 S L3 FULL
L8	0 S L5 NOT L6

FILE 'CAPLUS' ENTERED AT 14:17:26 ON 27 JUL 2005

L9	6 S L4
L10	104 S L5
L11	104 S L6
L12	2 S L7
L13	268877 S PHOTORESIST OR PHOTSENSITIVE OR MONOMER OR PHOTOREACTIVE OR
L14	12 S (L9 OR L10 OR L11 OR L12) AND L13

=>

L14 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2002:131242 CAPLUS

DN 136:191756

TI Manufacture of solid dispersion of photographic useful compound and thermographic material using it

IN Toda, Satoru

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 41 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002055405	A2	20020220	JP 2000-240658	20000809

PRAI JP 2000-240658 20000809

AB A colorless water-insol. organic compound is dispersed in a medium and heat-treated for 2-300 h at temperature higher than that at the dispersion.

The

organic compound may be a polyhalomethyl compound a bisphenol compound, or a compound which can form H-bond with a bisphenol compound The obtained dispersion and photothermog. material comprising a **photosensitive** Ag halide, a non-**photosensitive** organic Ag salt, a reducing agent, the dispersion, and a binder are also claimed. The dispersion shows good storage stability and coatability.

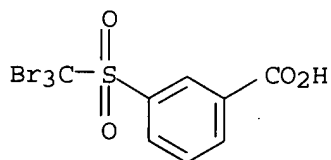
IT 299445-80-0

RL: PEP (Physical, engineering or chemical process); PYP (Physical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(photothermog. material using solid dispersion of photog. useful compound)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2001:356501 CAPLUS

DN 134:374096

TI Heat-developable photographic material containing polyhalogenide

IN Fukui, Kota; Takasaki, Masaru; Watanabe, Katsuyuki

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 36 pp.

CODEN: JKXXAF

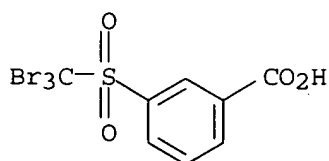
DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001133925	A2	20010518	JP 2000-245689	20000814
	US 6368782	B1	20020409	US 2000-644531	20000824
	US 2002048734	A1	20020425	US 2001-928520	20010814
PRAI	JP 1999-236306	A	19990824		
	JP 2000-245689	A	20000814		

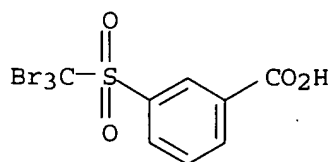
OS MARPAT 134:374096
 AB The material comprises a photothermog. layer containing ≥ 1 **photosensitive** Ag halide with average particle diameter 0.001-0.06 μm containing ≥ 2 organic polyhalogenide including ≥ 1 $\text{W1W2NCOLnQY1CZ1Z2X1}$ (Z1 , Z2 = halogen; X1 = H, electron-withdrawing group; Y1 = CO, SO_2 ; Q = arylene, bivalent heterocycle; L = linking group; W1 , W2 = H, alkyl, aryl, heterocycle; n = 0, 1), a light-insensitive organic Ag salt, a reducing agent, and a binder. The material prevents reduction of the sensitivity in storage at high temperature and is suitable for imaging for medical diagnosis and printing plate making.
 IT **299445-80-0**
 RL: MOA (Modifier or additive use); USES (Uses)
 (heat-developing photog. material containing polyhalogenide for retention of sensitivity in storage at high temperature)
 RN 299445-80-0 CAPLUS
 CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2001:143816 CAPLUS
 DN 134:200588
 TI Photothermographic material containing water dispersing agent
 IN Fukui, Kota; Watanabe, Katsuyuki; Takasaki, Suguru
 PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 33 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001056526	A2	20010227	JP 1999-231780	19990818
PRAI	JP 1999-231780		19990818		
OS	MARPAT 134:200588				

AB The material comprises an image forming layer containing ≥ 1 **photosensitive** Ag halide, a light insensitive Ag salt, a reducing agent, a binder, 0.001-1 mol/Ag-mol of aromatic mercapto or aromatic disulfide compound, and water-dispersion of ≥ 1 $\text{W1W2NCOLnQY1CZ1Z2X1}$ (Z1 , Z2 = halo; X1 = H, electron attractive group; Y1 = CO, SO_2 ; Q = arylene, bivalent heterocycle; L = linkage; W1 , W2 = H, alkyl, aryl, heterocycle; n = 0, 1) on ≥ 1 side of a support. It showed high sensitivity and improved image stability, suitable for medical and photomech. process.
 IT **299445-80-0P**
 RL: PNU (Preparation, unclassified); RCT (Reactant); PREP (Preparation);
 RACT (Reactant or reagent)
 (preparation of polyhalo compound)
 RN 299445-80-0 CAPLUS
 CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:723392 CAPLUS

DN 133:303620

TI Heat development photographic material containing organic polyhalo compound

IN Watanabe, Katsuyuki

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 40 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000284412	A2	20001013	JP 1999-90095	19990330
PRAI	JP 1999-90095		19990330		

OS MARPAT 133:303620

AB The title **photosensitive** material contains (a) a reducible Ag salt, (b) a reducing agent, (c) a binder, and (d) ≥ 1 polyhalo compound WLnQYlCXlZlZ2 (Z1, Z2 = halo; Xl = H, electron-attracting group; Yl = CO, SO2; Q = arylene, divalent heterocyclic group; L = linking group; W = Ag halide-adsorbing group containing ≥ 1 of C, N, S, O, and Se; n = 0 or 1). The material can be produced inexpensively and shows low fog and improved storage stability.

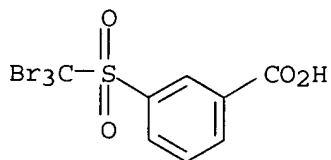
IT **299445-80-0P**

RL: PNU (Preparation, unclassified); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(preparation of organic polyhalo compound fog inhibitor)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:723391 CAPLUS

DN 133:303619

TI Heat development **photosensitive** material for photomechanical process

IN Fukui, Kota; Oya, Toyoharu

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 56 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 2000284409 A2 20001013 JP 1999-89561 19990330
 PRAI JP 1999-89561 19990330

OS MARPAT 133:303619

AB The title **photosensitive** material, containing a non-**photosensitive** organic Ag salt, a **photosensitive** Ag halide, and a binder on a support, contains, on the Ag halide-containing image-forming layer side, a compound WLnQY1CX1Z1Z2 (Z1, Z2 = halo; X1 = H, electron-attracting group; Y1 = CO, SO2; Q = arylene, divalent heterocyclic group; L = linking group; W = carboxyl or its salt, sulfo or its salt, phosphoric acid, OH, quaternary ammonium, polyethyleneoxy; n = 0 or 1) and ≥ 1 selected from a compound X11JmB1 (X11 = residue of photog. inhibitor having N-containing heterocycle; J = divalent linking group; B1 = ballast; m ≥ 1), a polymer having a repeating unit derived from a compound Q1X12 (Q1 = ethylenic unsatd. group, ethylenic unsatd. group-containing group; X12 = residue of photog. inhibitor having N-containing heterocycle), and a compound A1X13 (A1 = water soluble group-containing group; X13 = residue of photog. inhibitor having N-containing heterocycle). The material for scanner and image setter shows high photog. properties and prevents black spot formation even after storage.

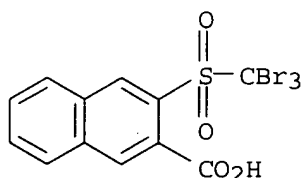
IT 253143-84-9 299446-56-3

RL: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)

(heat-developable photog. material containing organic polyhalo compound and development inhibitor)

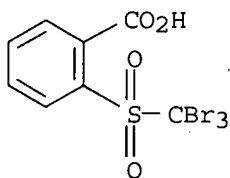
RN 253143-84-9 CAPLUS

CN 2-Naphthalenecarboxylic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 299446-56-3 CAPLUS

CN Benzoic acid, 2-[(tribromomethyl)sulfonyl]-, potassium salt (9CI) (CA INDEX NAME)



● K

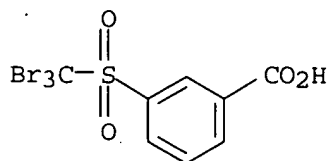
IT 299445-80-0P

RL: DEV (Device component use); MOA (Modifier or additive use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)

(heat-developable photog. material containing organic polyhalo compound and development inhibitor)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2000:723390 CAPLUS
 DN 133:303618
 TI Heat development **photosensitive** material for photomechanical process
 IN Ito, Tadashi
 PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 48 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000284407	A2	20001013	JP 1999-87972	19990330
PRAI	JP 1999-87972		19990330		

OS MARPAT 133:303618

AB The title **photosensitive** material, containing a non-**photosensitive** Ag salt, a **photosensitive** Ag halide, and a binder on a support, employs ≥ 2 kinds of Ag halides which are independently formed and are different in sensitivity for the **photosensitive** Ag halide and contains ≥ 1 compound selected from a substituted alkene derivative CR1Z:CR2R3, a substituted isoxazole derivative I, and an acetal compound CHXYCHAB (R1-3 = H, substituent; Z = electron-attracting group, silyl; R1 and Z, R2 and R3, R1 and R2, and R3 and Z may link each other to form a cyclic structure; R4 = substituent; X, Y = H, substituent; A, B = alkoxy, alkylthio, alkylamino, aryloxy, arylthio, anilino, heterocyclic oxy, heterocyclic thio, heterocyclic amino, X and Y and A and B may link each other to form a cyclic structure) in the Ag halide-containing image-forming layer side. The material for scanner and image setter shows low fog and high sensitivity and contrast and provides high Dmax images with good dot reproducibility.

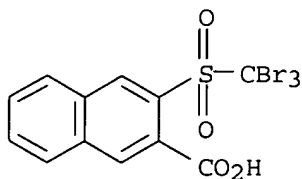
IT 253143-84-9

RL: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)

(fog inhibitor; heat-developable photog. material containing two kinds of **photosensitive** silver halides and nucleating agent)

RN 253143-84-9 CAPLUS

CN 2-Naphthalenecarboxylic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



IT 299445-80-0P

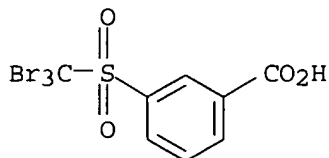
RL: DEV (Device component use); MOA (Modifier or additive use); PNU

(Preparation, unclassified); PREP (Preparation); USES (Uses)

(fog inhibitor; heat-developable photog. material containing two kinds of **photosensitive** silver halides and nucleating agent)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:723386 CAPLUS

DN 133:303615

TI Heat development photographic material for scanner and image setter

IN Ito, Tadashi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 48 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000284401	A2	20001013	JP 1999-88495	19990330
PRAI	JP 1999-88495		19990330		

OS MARPAT 133:303615

AB The material comprises an image forming layer containing ap non-**photosensitive** Ag salt, a **photosensitive** Ag halide with AgCl content ≥60 mol%, and a binder on a support of which image forming layer side surface contains ≥1 of a substituted alkene derivative R1ZC:CR2R3 (R1-3 = H, substituent; Z = electron attractive group, silyl; R1 and Z, R2 and R3, R1 and R2, and R3 and Z may form a ring structure), a substituted isoxazole derivative I (R4 = substituent), or an acetal compound XYCHCHAB (X, Y = H, substituent; A, B = alkoxy, alkylthio, alkylamino, aryloxy, arylthio, anilino, heterocyclic oxy, heterocyclic thio, heterocyclic amino; X and Y and A and B may form a ring structure). It showed low fog and high sensitivity, contrast, and maximum d., suitable for photog. printing plate use.

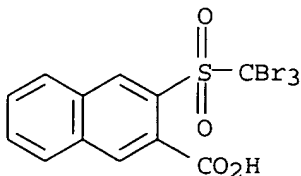
IT 253143-84-9

RL: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)

(fog inhibitor; heat-developable photog. material containing alkene, isoxazole, or acetal compound as nucleating agent)

RN 253143-84-9 CAPLUS

CN 2-Naphthalenecarboxylic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)

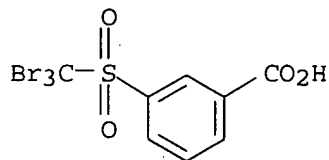


IT 299445-80-0P

RL: DEV (Device component use); MOA (Modifier or additive use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses) (fog inhibitor; heat-developable photog. material containing alkene, isoxazole, or acetal compound as nucleating agent)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:723384 CAPLUS

DN 133:303613

TI Heat development **photosensitive** material for photomechanical process and manufacture thereof

IN Ezoe, Toshihide; Kawato, Koji; Suzuki, Hiroyuki

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000284399	A2	20001013	JP 1999-87297	19990329
PRAI	JP 1999-87297		19990329		

OS MARPAT 133:303613

AB The title **photosensitive** material, containing a non-**photosensitive** Ag salt, a **photosensitive** Ag halide, and a binder on a support, contains a nucleating agent and ≤ 5 mmol/mol Ag of HCO₂H or its salt on the side possessing the Ag halide. The title process involves a step of adding the nucleating agent by using its solution or dispersion in which the concentration of HCO₂H or its salt to the agent is ≤ 10 mol%. The material for scanner and image setter shows super-high contrast, low fog, and little black spot and provides high Dmax images with good dot reproducibility.

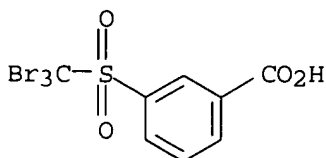
IT 299445-80-0P

RL: DEV (Device component use); MOA (Modifier or additive use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)

(formic acid content-controlled heat-developable photog. material containing nucleating agent and fog inhibitor)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



L14 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:705173 CAPLUS

DN 133:288774
 TI Heat-developable **photosensitive** material
 IN Goto, Takahiro; Ezoe, Toshihide; Suzuki, Hiroyuki; Sakai, Minoru; Maeda, Hideki; Inoue, Nobuaki; Takasaki, Masaru
 PA Fuji Photo Film Co., Ltd., Japan
 SO Eur. Pat. Appl., 110 pp.
 CODEN: EPXXDW

DT Patent
 LA English

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1041434	A1	20001004	EP 2000-106072	20000330
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2000284408	A2	20001013	JP 1999-88496	19990330
	JP 2000284402	A2	20001013	JP 1999-89709	19990330
	JP 2000284413	A2	20001013	JP 1999-90126	19990330
	JP 2000284405	A2	20001013	JP 1999-90152	19990330
	US 6344313	B1	20020205	US 2000-538727	20000330
PRAI	JP 1999-88496	A	19990330		
	JP 1999-89709	A	19990330		
	JP 1999-90126	A	19990330		
	JP 1999-90152	A	19990330		

OS MARPAT 133:288774

AB An object of the present invention is to provide a heat-developable **photosensitive** material of improved fluctuation of photog. performance (sensitivity, D_{min}) arisen from fluctuation of development temperature condition (temperature, time) and storage time after heat development.

According to the present invention, there is provided a heat-developable **photosensitive** material, wherein the **photosensitive** material comprises, on a support, an image-forming layer containing at least (a) non-**photosensitive** organic silver salt, (b) **photosensitive** silver halide, (c) a reducing agent, and (d) a binder, and a protective layer on the image-forming layer, polymer latexes are used as binders of the image-forming layer and the protective layer, and the **photosensitive** material further comprises, on the image-forming layer side, (e) a nucleating agent and (f) one or more compds. represented by formula I (Z1, Z2 = a halogen atom; X1 = H, an electron withdrawing group; Y1 = -CO- group or -SO2- group; Q = an arylene group which may have a substituent or a divalent heterocyclic group which may have a substituent; L = a linking group; W = carboxyl group or a salt thereof, sulfo group or a salt thereof, phosphoric acid group, hydroxyl group, a quaternary ammonium group, or a polyethyleneoxy group; n = 0, 1).

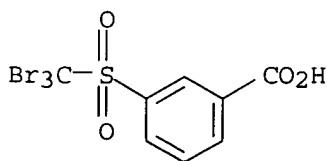
IT 299445-80-0P

RL: RCT (Reactant); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)

(heat developable **photosensitive** material)

RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



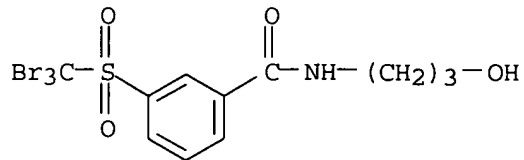
IT 299446-48-3 299446-52-9 299446-56-3

299446-60-9

RL: TEM (Technical or engineered material use); USES (Uses)
(heat developable **photosensitive** material)

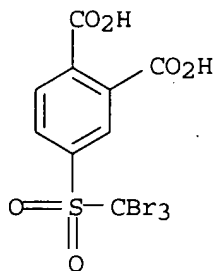
RN 299446-48-3 CAPLUS

CN Benzamide, N-(3-hydroxypropyl)-3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



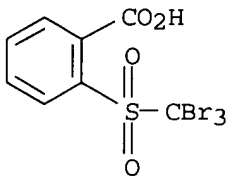
RN 299446-52-9 CAPLUS

CN 1,2-Benzenedicarboxylic acid, 4-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 299446-56-3 CAPLUS

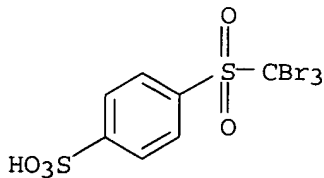
CN Benzoic acid, 2-[(tribromomethyl)sulfonyl]-, potassium salt (9CI) (CA INDEX NAME)



● K

RN 299446-60-9 CAPLUS

CN Benzenesulfonic acid, 4-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



ALL CITATIONS AVAILABLE IN THE RE FORMAT

L14 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:705172 CAPLUS

DN 133:288773

TI Heat-developable **photosensitive** material and method for forming image using the same

IN Ito, Tadashi; Watanabe, Katsuyuki; Katoh, Kazunobu; Sakai, Minoru

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 85 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1041433	A1	20001004	EP 2000-106071	20000330
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2000284396	A2	20001013	JP 1999-89674	19990330
	JP 2000284411	A2	20001013	JP 1999-89882	19990330
	JP 2000347342	A2	20001215	JP 1999-281747	19991001
	US 6329127	B1	20011211	US 2000-537764	20000330
PRAI	JP 1999-89674	A	19990330		
	JP 1999-89882	A	19990330		
	JP 1999-90125	A	19990330		
	JP 1999-281747	A	19991001		

AB An object of the present invention is to provide a heat-developable **photosensitive** material of less heat development temperature and humidity dependency, which is unlikely to be affected by uneven temperature distribution in heat development apparatuses and humidity condition, and can stably form uniform images, in particular, a heat-developable **photosensitive** material of improved stability of coating solns. overtime, which can form uniform ultrahigh contrast images without unevenness, which are suitable for mech. processes, and exhibit suppressed fluctuation of photog. performance depending on the storage condition. According to the present invention, there is provided a heat-developable **photosensitive** material having at least one **photosensitive** image-forming layer comprising an organic silver salt, a **photosensitive** silver halide, a reducing agent and an organic binder, wherein at least one of the **photosensitive** image-forming layer and a layer adjacent to the **photosensitive** image-forming layer contains a first halogen-releasing precursor having at least one dissociative or hydrophilic substituent and a second hydrophobic halogen-releasing precursor.

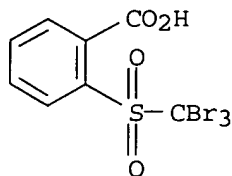
IT 253143-83-8 253143-84-9 253143-86-1

299445-80-0 299445-83-3

RL: TEM (Technical or engineered material use); USES (Uses)
 (halogen releasing precursor; heat developable **photosensitive** material and method for forming image using the same)

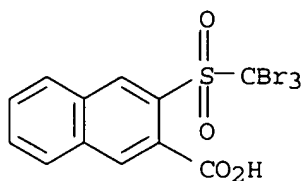
RN 253143-83-8 CAPLUS

CN Benzoic acid, 2-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



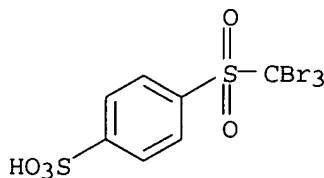
RN 253143-84-9 CAPLUS

CN 2-Naphthalenecarboxylic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 253143-86-1 CAPLUS

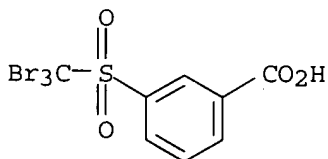
CN Benzenesulfonic acid, 4-[(tribromomethyl)sulfonyl]-, sodium salt (9CI) (CA INDEX NAME)



● Na

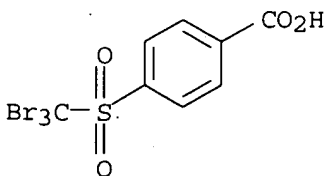
RN 299445-80-0 CAPLUS

CN Benzoic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 299445-83-3 CAPLUS

CN Benzoic acid, 4-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RE.CNT 1 THERE ARE 1 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L14 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2000:20335 CAPLUS

DN 132:71406

TI Heat-sensitive image recording material and heat development
photosensitive image recording material

IN Fujiwara, Yoshinori; Inoue, Rikio

PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 28 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000002963	A2	20000107	JP 1998-181459	19980612
	US 2002015926	A1	20020207	US 1999-330195	19990611
	US 6468730	B2	20021022		
PRAI	JP 1998-181459	A	19980612		

OS MARPAT 132:71406

AB The former material has layers containing a nonphotosensitive organic Ag salt, its reducing agent, and a binder on a support, in which at least one of the layers contains a compound X1X2X3CYLZ (X1, 2 = halogen; X3 = H, halogen, monovalent substituent; L = divalent organic group; Y = heteroatom-containing divalent organic group, single bond; Z = acidic functional group, its salt). The latter material has layers containing a **photosensitive** Ag halide salt, a binder, and the compound on a support. The material gives good images with excellent storage stability.

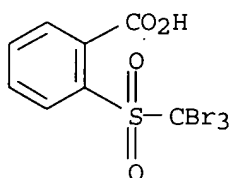
IT 253143-83-8 253143-84-9 253143-86-1

RL: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)

(thermal printing or heat development image recording material having halogen-containing organic compound)

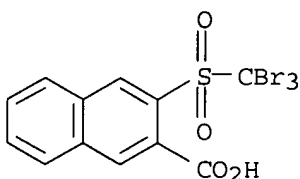
RN 253143-83-8 CAPLUS

CN Benzoic acid, 2-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME).



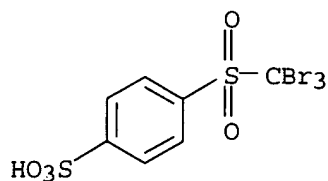
RN 253143-84-9 CAPLUS

CN 2-Naphthalenecarboxylic acid, 3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 253143-86-1 CAPLUS

CN Benzenesulfonic acid, 4-[(tribromomethyl)sulfonyl]-, sodium salt (9CI) (CA INDEX NAME)



● Na

L14 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 1987:565342 CAPLUS
 DN 107:165342
 TI Silver halide photographic **photosensitive** materials
 IN Sato, Koichi; Ishikawa, Hisashi
 PA Konishiroku Photo Industry Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 14 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 62027739	A2	19870205	JP 1985-166554	19850727
PRAI	JP 1985-166554		19850727		

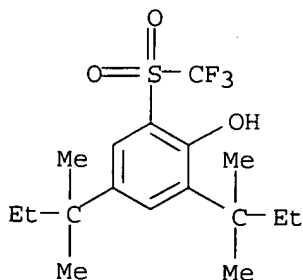
AB The claimed photog. materials contain a phenolic compound I (R1, R2 = H, alkyl; R1 and R2 can not be H simultaneously; R3 = halo, electron-attractive group, excluding COR4 and SOR5; R4 = alkyl, aryl, heterocyclyl, alkoxy, aryloxy, heterocyclyoxy; R5 = alkyl, aryl, heterocyclyl) which does not form color. The photog. materials show improved coloration characteristics.

IT **110581-99-2**

RL: USES (Uses)
 (photog. coupler solvent)

RN 110581-99-2 CAPLUS

CN Phenol, 2,4-bis(1,1-dimethylpropyl)-6-[(trifluoromethyl)sulfonyl]- (9CI)
 (CA INDEX NAME)



=>

L10 ANSWER 2 OF 15 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:934211 CAPLUS

DN 141:403508

TI Producing method of **photosensitive** planographic printing plate

IN Hirabayash, Kazuhiko

PA Japan

SO U.S. Pat. Appl. Publ., 41 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2004219459	A1	20041104	US 2004-828081	20040420
	JP 2004325726	A2	20041118	JP 2003-119577	20030424
PRAI	JP 2003-119577	A	20030424		

OS MARPAT 141:403508

AB The object of the present invention is to provide a method for producing a **photosensitive** planog. printing plate having a high sensitivity and high printing durability and a low manufacturing cost. A method for producing a **photosensitive** planog. printing plate containing the steps of: (i) carrying out electrolysis to an aluminum support in an aqueous solution of hydrochloric acid or nitric acid so as to provide the aluminum support with a roughened surface; (ii) coating a **photosensitive** composition on the roughened surface of the aluminum support to obtain a **photosensitive** layer, the **photosensitive** composition containing: (A) a **monomer** having an ethylenic double bond which is addition polymerizable; (B) a photoinitiator composition containing an iron arene complex

compound; and (C) a polymer binder, (iii) drying the **photosensitive** layer.

IT 17025-47-7 85095-67-6 263339-82-8

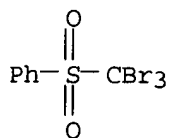
299445-94-6 299446-72-3

RL: TEM (Technical or engineered material use); USES (Uses)

(producing method of **photosensitive** planog. printing plate)

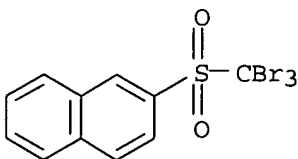
RN 17025-47-7 CAPLUS

CN Benzene, [(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



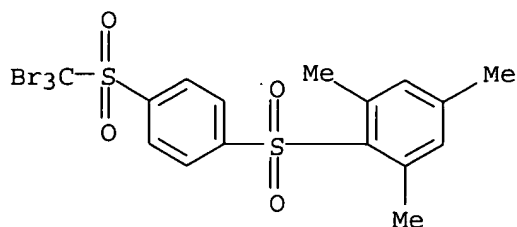
RN 85095-67-6 CAPLUS

CN Naphthalene, 2-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)

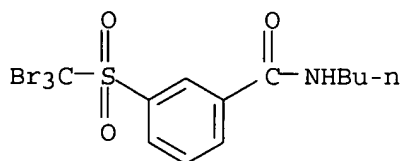


RN 263339-82-8 CAPLUS

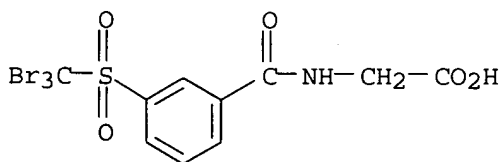
CN Benzene, 1,3,5-trimethyl-2-[[4-[(tribromomethyl)sulfonyl]phenyl]sulfonyl]- (9CI) (CA INDEX NAME)



RN 299445-94-6 CAPLUS
 CN Benzamide, N-butyl-3-[(tribromomethyl)sulfonyl]- (9CI) (CA INDEX NAME)



RN 299446-72-3 CAPLUS
 CN Glycine, N-[3-[(tribromomethyl)sulfonyl]benzoyl]- (9CI) (CA INDEX NAME)



L10 ANSWER 3 OF 15 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:901086 CAPLUS

DN 141:386370

TI Dry film **photoresist** containing vinyl copolymer having carboxy and urea groups

IN Wakata, Yuichi; Takahashi, Hidetomo

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 34 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004302371	A2	20041028	JP 2003-98184	20030401
PRAI	JP 2003-98184		20030401		

AB Disclosed is the dry film **photoresist** comprising a flexible translucent film support and a **photosensitive** resin composition layer formed thereon, wherein the layer is made from (A) a vinyl polymer binder component having a carboxy group in a repeating unit and a urea group in a side chain of another repeating unit, (B) a polymerizable compound **monomer** component having ≥ 2 ethylenic unsatd. bonds, and (C) a photopolymer. initiator. The dry film **photoresist** is used for a manufacture of a printed circuit board having a through hole.

IT 17025-47-7, Phenyltribromomethylsulfone

RL: CAT (Catalyst use); USES (Uses)

(photopolymer. initiator; dry film **photoresist** containing vinyl

copolymer having ca

=> d his

(FILE 'HOME' ENTERED AT 14:24:52 ON 27 JUL 2005)

L1 FILE 'REGISTRY' ENTERED AT 14:26:20 ON 27 JUL 2005
STRUCTURE UPLOADED

L2 FILE 'REGISTRY' ENTERED AT 14:26:36 ON 27 JUL 2005
STRUCTURE UPLOADED
L3 3032 S L2 FULL

L4 FILE 'CAPLUS' ENTERED AT 14:27:08 ON 27 JUL 2005
1466 S L3
L5 90733 S PHOTORESIST OR PHOTOSENSITIVE OR PHOTOREACTIVE
L6 286 S L4 AND L5
L7 425239 S SILVER OR AG
L8 156 S L6 NOT L7
L9 174885 S MONOMER
L10 15 S L8 AND L9

=>

ethanol	ml	
NaOH 1M	40	
"Teepol" (Registered Trade Mark)	10	65
	0.2	

The solvent removed the non-light-struck areas of the coating. The remaining areas of the coating were then de-sensitised to light for which purpose a "Kodak" (Registered Trade Mark) Polymatic desensitiser gum solution was used.

Example 2

The procedure described in Example 1 was repeated using, instead of the 0.25 ml of 6.45% by weight solution of carboxymethylthioferrocene in dichloroethane, 0.25 ml of a 10.4% by weight solution of 1,1'-dicinnamoyl ferrocene in dichloroethane. The image obtained was somewhat fainter than that obtained in Example 1.

Example 3

The procedure described in Example 1 was repeated except that the composition was prepared from:

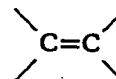
A composition was prepared from:

10% by weight solution in dichloroethane of the polymer product of Preparation 7	ml	
5% by weight solution in dichloroethane of ferrocene	5	90
Plasticiser SR 295	0.25	
	0.08	

and the plate was imagewise exposed for 10 minutes instead of 5 minutes. The lithographic plate thus produced gave, on inking, a good image.

WHAT WE CLAIM IS:—

1. A composition comprising: 100
(i) a reactive polymer containing repeating units comprising a group of formula



and repeating units, which may be the same or different, comprising a group which contains two or three chlorine or bromine atoms bonded to a single carbon atom, and (ii) a metallocene as herein defined.

2. A composition according to claim 1 in which one or each of the two cyclopentadienyl groups of the metallocene is substituted with a cinnamoyl group. 110

3. A composition according to claim 1 in which one or each of the two cyclopentadienyl groups of the metallocene is substituted with a carboxymethyl thio group. 115

4. A composition according to claim 2 in

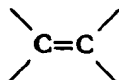
life of the layer and/or which improves the ink-accepting properties of the layer.

11. A material according to claim 10 in which the said polyester is pentaerythritol tetracrylate.

12. A material according to claim 10 or to claim 11 in which the said layer contains, per 50 parts by weight of reactive polymer, from 1 to 5 parts by weight of metallocene and 8 parts by weight of polyunsaturated ester.

13. A material according to claim 9 substantially as described in Examples 1, 2 or 3.

14. A method of preparing a lithographic plate which comprises imagewise exposing the said layer of a lithographic material according to any of claims 9 to 13 to radiation, thereby to render the reactive polymer of the said layer in the radiation-struck portions of the said layer relatively insoluble compared with the reactive polymer of said layer in the non-radiation struck portions of the said layer and thereafter removing the relatively non-insolubilised portions of the said layer, thereby to provide ink-accepting areas which are constituted by the surface of the relatively insolubilised portions of the layer.



15. A lithographic plate which has been prepared by a method according to claim 14.

L. A. TRANGMAR, B.Sc., C.P.A.,
Agent for the Applicants.

by the Courier Press, Leamington Spa, 1977
 npton Buildings, London, WC2A 1AY, from
 ay be obtained.

Printed for Her Majesty's Stationery Office, by the Courier Press, Leamington Spa, 1977
Published by The Patent Office, 25 Southampton Buildings, London, WC2A 1AY, from
which copies may be obtained.

10/687,689, 7/28/05, RPA.

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
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L4	1	gb-1495529-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 16:24
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L6	0	arene near3 formual	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 16:26
L7	506	arene near3 formula	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 16:40
L8	2	hirabayash.in.	US-PGPUB; USPAT	OR	ON	2005/07/27 16:52
L9	1	metallocene same (trihalomethane or tribromomethane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/27 16:58
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